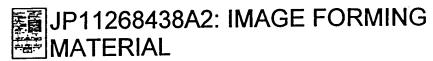


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Country:

JP Japan

Kind:

A2 Document Laid Open to Public Inspection

Inventor(s):

KAWAMURA KOICHI

Applicant(s):

FUJI PHOTO FILM CO LTD

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Issued/Filed Dates:

Oct. 5, 1999 / March 23, 1998

Application Number:

JP1998000074630

IPC Class:

B41N 1//14; G03F 7//004; G03F 7//032;

Abstract:

Problem to be solved: To provide an image forming material being suitable for a lithographic printing plate, which is excellent in image

forming properties (a sensitivity, a development latitude).

Solution: This image forming material contains a polymer binder which is water-insoluble and soluble with an alkali aqueous solution, and an infrared ray absorber having a thermally decomposable sulfonate group. At unexposed parts, the infrared absorber having the thermally decomposable sulfonate group reduces the melting speed of an alkali-soluble polymer binder, and at exposed parts, a sulfonic acid of a coloring matter which is generated by a

decomposition of the infrared ray absorber, increases the melting speed of the alkali-soluble polymer binder. By this method, a difference between both parts becomes larger, and a favorable.

image formation becomes possible.

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Family:

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Other Abstract Info:

CHEMABS 131(15)206999Q DERABS C1999-470981

Foreign References:

(No patents reference this one)

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What is claimed is:

- 1. A photosensitiv negative image recording material for a planographic printing plate having an image recording layer containing the following components on a support:
 - · a compound (A) which is degraded by the action of light or heat to generate an acid,
 - · a cross-linking agent (B) which cross-links in the presence of an acid,
 - at least one alkali-soluble resin (C).
 - an infrared absorbing agent (D), and
 - at least one amino acid or derivative thereof wherein the amino acid is selected from the group consisting of glycine. B-alanine, valine, norvaline, leucine, norleucine, phenylalanine, tyrosine, diiodotyrosine, surinamine, serine, proline, hydroxyproline, tryptophan, thyroxine, cystine, cysteine, .gamma.-aminobutyric acid, glutamine, lysine, hydroxylysine, arginine and histidine.

Background/Summary:

Show background/summary

Drawing Descriptions:

Show drawing descriptions

Description of Preferred Embodiments: Foreign References:

Show description of preferred embodiments

Publication	Country	Date	IPC Class
EP1997000784233	European Patent Office (EPO)	7 /1997	

Other Abstract Info:

CHEMABS 129(01)010678Y CHEMABS 129(01)010679Z DERABS C1998-337596 DERABS C1998-337597

Other References:

· A. Lamola. et al, Chemically Amplified Resists in Solid State Technology, Aug. 1991, pp. 53-60. (8 pages) 20 patents reference this [Article info]

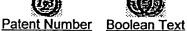
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